

ABSTRACT

An ultraviolet-curable resin composition comprises a phosphorus atom-containing photopolymerizable compound and a
5 carboxyl group-containing photopolymerizable compound and exhibits the surface tension at 25°C in the range of 30 to 50 mN/m. Preferably the composition comprises (a) a compound having one or more (meth)acryloyl groups in its molecule and a phosphorus atom, (b) a compound having one carboxyl group and one
10 (meth)acryloyl group in its molecule, (c) a compound having one or more (meth)acryloyl groups in its molecule, (d) a leveling agent, and (e) a photoinitiator. The ultraviolet-curable resin composition is useful as a protective material for etching, particularly as a back-coating material in the production of a
15 shadow mask.